

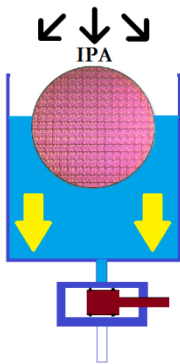


The UltraFine Family of Etch, Clean & Dry Products are distinctively designed to meet the specific process needs of today's leading-edge applications for Wafers, Photomask and Substrates.



About us

For over twenty years, Ultra *t* Equipment Company has provided equipment used in a wide variety of applications, ranging from cleaning to coating and developing to the microelectronic industry.

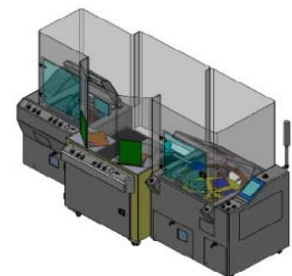


Ultra VaporDry System:

The Highly Efficient, Very Reliable & Cost Effective System is ideal for Drying Wafers, Photomask, & other Substrates. They can be configured for Megasonic & Low Pressure to Heaters, Brushes and more for different Process Chemistries and Dispense options. The Ultra *VaporDry* System combines Rapid and Effective Cleaning & Drying techniques from Variable Spin Speeds to add-on Drying modules. The system is designed with ultra-safety of the Operator with "Safety Rinses" of Chemicals prior to substrate access.

Get started right away with these Features

- Chemically Compatible for Hazardous Chemistries.
- Safety Interlocks & Double Containment.
- Designed for Maximum Laminar Flow.
- Clean & Dry Assist Included.
- Microprocessor Control - Configurable and Expandable.
- Power Lid for "Easy Substrate Access" and "Substrate Load/Unload".
- Keypad for "Ease of Recipe Creation".
- "Automated Error Reporting".
- Meets all SEMI S2/S8 and CE Guidelines.



Also available in "Fully Automated Cassette to Cassette handling"

Contact us

Phone: [(510) 440-3900] | Email: [sales@ultrat.com] | Web: [www.ultrat.com]